

Verkleg eðlisfræði:

Greina og skýrsluskrif

Kaflí 2

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Inngangur

- Greinar og skýrslur eru verkfærið sem notað er til að koma á framfæri nýjum uppgötvunum í vísindum
- Greinar og skýrslur fylgja staðlaðri uppbyggingu
- Tilvitnanir í fyrri verk fylgir líka stöðluðum venjum sem að einhverju leyti ræðst af fagsviðum
- Gröf þurfa að vera á tilteknu formi og fylgja tilteknum reglum

Uppbygging greinar

- Tilraunagrein samanstendur almennt af fimm köflum
 - **Abstract**
 - **Introduction**
 - **Expermental apparatus and method**
 - **Results**
 - **Discussion**
 - **Conclusion**

Uppbygging greinar

- Fræðileg samanstendur almennt af fimm köflum
 - **Abstract**
 - **Introduction**
 - **Model description eða Theory**
 - **Results**
 - **Discussion**
 - **Conclusion**

Uppbygging greinar

- **Abstract**

- Samantekt um hvað gert var, hverjar eru helstu niðurstöðurnar, og hvað er nýtt
- Þarf að vera mjög hnitmiðað
- Inniheldur allar helstu niðurstöður

Uppbygging greinar

- **Introduction** - Inngangur

- Hefst á því að tengja viðkomandi rannsókn við stóru myndina – 2 til 3 setningar
- Ýtarleg en hnitmiðuð samantekt á því sem að gert hefur verið í eins eða svipuðum rannsóknum
- Yfirlýsing um hvað er verið að gera með þessari rannsókn sem er nýtt og hvernig það bætir við núverandi þekkingu

Uppbygging greinar

- **Experimental apparatus and method**

- Fjallað er um uppsetningu tilraunar og þær aðferðir sem notaðar eru
- Hér eru líka rædd þau fræði og jöfnur sem beitt er við úrinnslu gagna
- Lýsing á tilraunauppstillingunni á að innhalda nægilega miklar upplýsingar til að hægt sé að endurtaka tilraunina
 - * Hvaða tæki eru notuð
 - * Allir helstu stærðir – stærðir, hitastig, þrýstingur o.s.frv.

Uppbygging greinar

- **Model description** eða **Theory**
 - Fjallað er um uppbyggingu líkans sem notað er eða að fræðin sem beitt er eru undirbyggð
 - Lýsingin á líkani og stærðum sem notaðar eru þarf að era nægilega nákæm til að lesandinn geti sett upp eigið líkan til að endurtaka reikningana
 - Fyrir tölulega reikninga þarf að vera lýsing á forriti sem notað er og öllum upphafsgildum og stuðlum sem notaðir eru við reikninga

Uppbygging greinar

- **Results**

- Hér er farið yfir helstu niðurstöður
- Flest gröfin eru hér sýnd og rædd
- Það þarf að vísa í öll gröf úr texta
- Texti undir mynd (figure caption) þarf að vera ítarlegur. Stundum öðlast myndin og myndatextinn sjálfstætt líf.

Uppbygging greinar

- **Discussion**

- Hér er fjallað um niðurstöðurnar og þær bornar saman við hvað aðrir hafa séð
 - * Hvað er öðruvísi og hvers vegna ?
- Hér má líka líta fram á veginn, hvað hafa niðurstöðurnar í för með sér og hver geta verið næstu skref
- Oft er köflunum **Results** og **Discussion** slegið saman í **Results and discussion**

Uppbygging greinar

- **Conclusion** eða **Summary**
 - Samantekt um hvað gert var og hverjar eru helstu niðurstöðurnar
 - Inniheldur allar helstu niðurstöður

Uppbygging greinar

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Plasma parameters in a planar dc magnetron sputtering discharge of argon and krypton

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Abstract. The electron energy distribution function (EEDF) and plasma parameters in a planar dc magnetron sputtering discharge in argon and krypton were determined using a Langmuir probe. Two groups of electrons are observed in the discharge. The electron temperature of the cold electrons is roughly independent of the discharge pressure, while the electron temperature of the hot electrons decreases with increased discharge pressure. The electron density increases with increased pressure and is roughly a factor of 2–3 higher for a krypton discharge than for an argon discharge.

1. Introduction

The dc magnetron sputtering discharge has found widespread use in coating processes, particularly for deposition of thin metallic films. A typical dc planar magnetron discharge operates at a pressure of 1–10 mTorr with a magnetic field strength of 0.01–0.05 T and cathode potentials 300–700 V [1]. There have been a number of investigations of the spatial variation of the plasma parameters in a dc planar magnetron sputtering discharge [2, 3, 4, 5, 6]. Field et al. [5] find the electron density is highest in and near the magnetic trap above the end region (see text) and is at a local minimum above the wall region in the center of the cathode and near the edges of the cathode. Electron energy distribution functions (EEDF) are found to differ Maxwellian like or bi-Maxwellian like in nature, depending on pressure and spatial location [3, 6]. Maxwellian like electron energy distributions are found in or near the magnetic trap and bi-Maxwellian distributions are found further away from the cathode target [3]. The electron temperature and the electron density decrease with distance from the cathode target [2]. Outside the magnetic trap the plasma potential is generally found to have weak dependence on spatial location and pressure [3, 5].

Here we explore the spatial dependence of the electron energy distribution function (EEDF) and plasma parameters, electron density, electron temperature, and the plasma potential, in a planar dc magnetron sputtering discharge using a Langmuir probe. A comparison is made between argon and krypton sputtering gas.

2. Experimental apparatus and method

A Langmuir probe is used to measure the spatial variation of the electron energy distribution function (EEDF) in a dc magnetron sputtering discharge. The Langmuir probe was made of

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a tungsten wire 127 μ m in diameter and 5 mm long. A standard planar magnetron source was operated with a copper (Cu) target 76.2 mm in diameter. The sputtering target, the cathode, was located inside a stainless steel chamber, 200 mm in diameter and 220 mm long. The magnetron is operated in a constant power mode at 100 W. The target voltage for the scan was in the range 380 $\pm$ 5 V to 420 $\pm$ 5 V, and the target current was in the range 220 $\pm$ 15 mA to 260 $\pm$ 10 mA. The circular water-cooling system cooled the copper (Cu) target while the sputtering was in progress. The base pressure was maintained below 10^{-7} Torr, with a turbo molecular pump. Argon (Ar) and krypton (Kr) of purity 99.9997 % were used as discharge gases. The discharge was operated at four different pressures: 3, 5, 10 and 15 mTorr. The Langmuir probe was moved in 20 mm steps away from the cathode target along the discharge center axis in the range 20 mm to 120 mm from the target surface. The Langmuir probe current-voltage (I – V) characteristic was recorded, the current was monitored by measuring the voltage over an 10 k Ω resistor as well as the voltage applied to the Langmuir probe. The probe current and voltage were collected with a 12-bit A/D converter and stored on a computer. The second derivative of the probe I – V curve was obtained by numerically differentiating and filtering [7] the measured I – V curve to determine the electron energy distribution function (EEDF) from Druyvesteyn formula [8, p. 191]. The electron density was found by

$$n_e = \int_0^\infty n_e(E) dE \quad (1)$$

where E is the electron energy. The electron energy probability function (EEPF) is $g(E) = E^{-3/2} n_e(E)$. Kagan and Post [9] showed that the magnetic field does not disturb the I – V characteristic of a cylindrical Langmuir probe, if the probe radius is small, it is placed perpendicular to the field and the Larmor radius of the electrons is much larger than the probe radius. The magnetic flux density is below 30 mT at the target surface. Thus, the probe radius is much smaller than the Larmor radius of the electrons and the distortion of the low energy part of the I – V characteristic can be considered negligible.

3. Results and discussion

Figure 1 shows the electron energy probability function (EEPF) for an argon discharge at 5 mTorr in the range 20–120 mm from the target surface. Two groups of electrons are apparent in the discharge. Similarly, two groups of electrons are apparent in the krypton discharge as shown in figure 2. Figure 3 shows the electron temperature versus distance from target along the center axis for argon discharge. It has a group of cold electrons with electron temperature in the range 0.6–1.2 eV and hot electrons with electron temperature in the range 1.3–5 eV. For both groups the electron temperature decreases with increased distance from the cathode target. The electron temperature of the cold electrons is roughly independent of the discharge pressure, while the electron temperature of the hot electrons decreases with increased discharge pressure. The plasma potential is in the range 1.4–1.8 V and is spatially uniform outside the magnetic trap in the range 20–120 mm and increases with increased discharge pressure. Thus, the cold electrons are trapped by this plasma potential. Figure 4 shows the electron temperature versus distance from target along the discharge center axis for krypton discharge. The krypton discharge has a group of cold electrons with electron temperature in the range 0.6–3.5 eV and a group of hot electrons with electron temperature in the range roughly 1 to 4 eV. Just as for the argon discharge, the electron temperature decreases with increased distance from the cathode target for both groups of electrons. The electron temperature of the cold electrons is roughly independent of the discharge pressure. The plasma potential is spatially flat in the range 1.35–2.2 V and increases with increased discharge pressure. The bi-Maxwellian like EEDF is commonly observed in the relative vicinity in magnetron sputtering discharges [3, 6, 10]. Sheridan et al. [3] claim that the hot electrons are not energetic enough to be the ones

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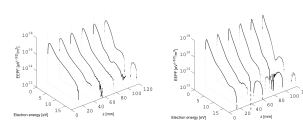


Figure 1. The electron energy probability function (EEDF) along the discharge center axis for argon discharge at 5 mTorr.

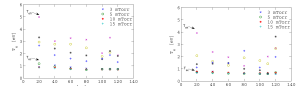


Figure 3. The electron temperature for hot electrons T_{eh} and cold electrons T_{ec} versus distance from target along the discharge center axis for argon discharge.

emitted from the target, but are created in the magnetic trap in the cathode fall region and drift to the sheath region under the influence of a diverging magnetic field [2, 10]. The low and flat distribution of the plasma potential traps the cold electrons. Thus, a bi-Maxwellian like electron energy distribution is observed in the sheath region. Figure 5 shows the electron density versus distance from target along the discharge center axis for an argon discharge. The electron density increases with increased pressure from about 2×10^{16} m $^{-3}$ at 3 mTorr to 10^{18} m $^{-3}$ at 15 mTorr. Furthermore, for pressure above 5 mTorr the electron density increases slightly with distance and peaks at roughly 80 mm from the target and then decreases again with further increase in distance. Figure 6 shows the electron density versus distance from target along the discharge center axis for krypton discharge. The electron density in a krypton

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discharge increases with increased pressure and is roughly a factor of 2–3 higher than for an argon discharge. Higher electron density is expected in a krypton discharge than for an argon discharge, since the ratio of electron impact ionization rate coefficient $k_{ei}/k_{ea} \approx 2.9$ for electron temperature of 2 eV and $k_{ei}/k_{ek} \approx 2.2$ for electron temperature of 3 eV [11].

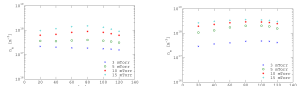


Figure 5. The electron density versus distance from target along the discharge center axis for argon discharge.

4. Conclusion

The electron energy distribution function (EEDF) and plasma parameters were determined along the axis of planar dc magnetron sputtering discharge in argon and krypton. Two groups of electrons are observed in the discharge. The electron density increases with increased pressure and is roughly a factor of 2–3 higher for a krypton discharge than for an argon discharge.

Acknowledgements

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Frá Sigurjonsson and Gudmundsson (2008)

Tilvitnanir

- Það eru all margar skilgreindar staðlaðar leiðir til að birta lista af greinum og bókum sem vitnað er í úr greinum eða skýrslum
- Fyrir *Journal of Physics: Conference Series* notar vancouver eða harvard staðalinn
- Í vancouver þá eru tilvitnanir númeraðar eftir því hvenær þær koma fyrir í textanum
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Tilvitnanir—vancouver

1. Introduction

The dc magnetron sputtering discharge has found widespread use in coating processes, particularly for deposition of thin metallic films. A typical dc planar magnetron discharge operates at a pressure of 1 – 10 mTorr with a magnetic field strength of 0.01 – 0.05 T and cathode potentials 300 – 700 V [1]. There have been a number of investigations of the spatial variation of the plasma parameters in a dc planar magnetron sputtering discharges [2, 3, 4, 5, 6]. Field et al. [5] find the electron density is highest in and near the magnetic trap above the etch region (race track) and is at a local minimum above the well region in the center of the cathode

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Tilvitnanir—chicago

for almost 200 years so the literature is rather extensive. Such a discussion can be found in a number of review articles (Druyvesteyn and Penning 1940, Francis 1956, Ingold 1978) and textbooks such as Roth (1995, chapter 9) and Raizer (1991, section 8.1).

As seen in figure 1, the dc glow discharge operates the discharge current range from μA to hundreds of mA (current

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Frá Guðmundsson and Hecimovic (2017)

Tilvitnanir-ieeeetr

A LARGE class of discharges makes use of electron trapping in crossed electric and magnetic fields, for example Hall thrusters [1], [2], magnetized microdischarges [3], and sputtering magnetrons [4]. It has been recognized that ionization and particle transport are governed by a host of waves and instabilities. Recent publications on instabilities in magnetrons focused on high-power impulse magnetron sputtering (HiPIMS); several groups showed pro-

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Gröf

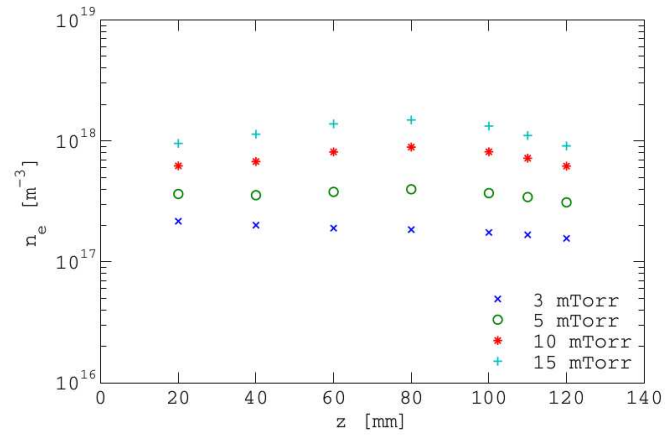


Figure 5. The electron density versus distance from target along the discharge center axis for argon discharge.

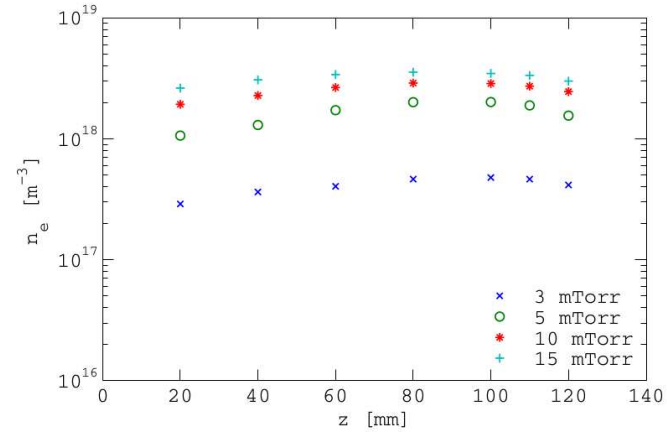


Figure 6. The electron density versus distance from target along the discharge center axis for krypton discharge.

Frá Sigurjonsson and Gudmundsson (2008)

Gröf

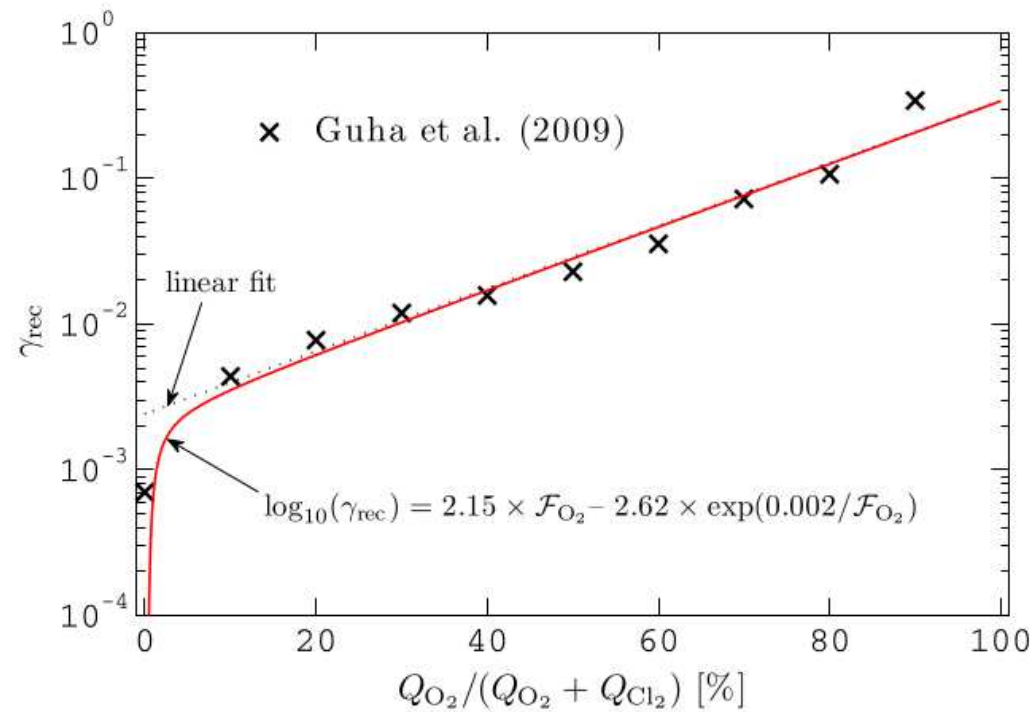


Figure 2. The wall recombination coefficient γ_{rec} for the production of ClO molecules from surface loss of Cl atoms. The experimental data (x) are derived from the measurements of Guha and Donnelly [14, 115].

Frá Thorsteinsson and Gudmundsson (2010)

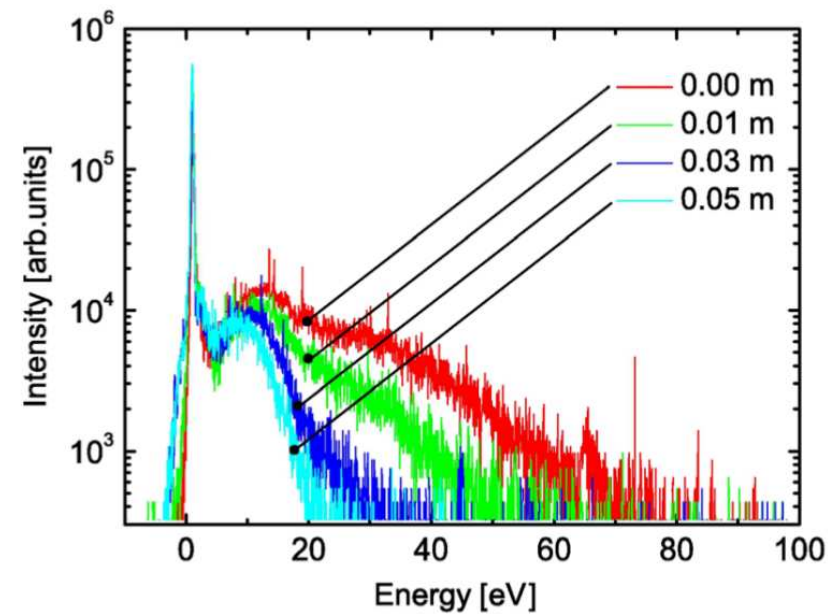


FIG. 10. (Color online) Time averaged ion energy distribution for Ti^+ ions at 0.53 Pa using 500 V HiPIMS pulses for different distances from the target surface. The average ion energy is found to be around 18 eV when measured at the target position. The mass spectrometer was inserted from the side of the chamber (at $z = 0.00$ m). From Lundin *et al.* (Ref. 168).

Gröf

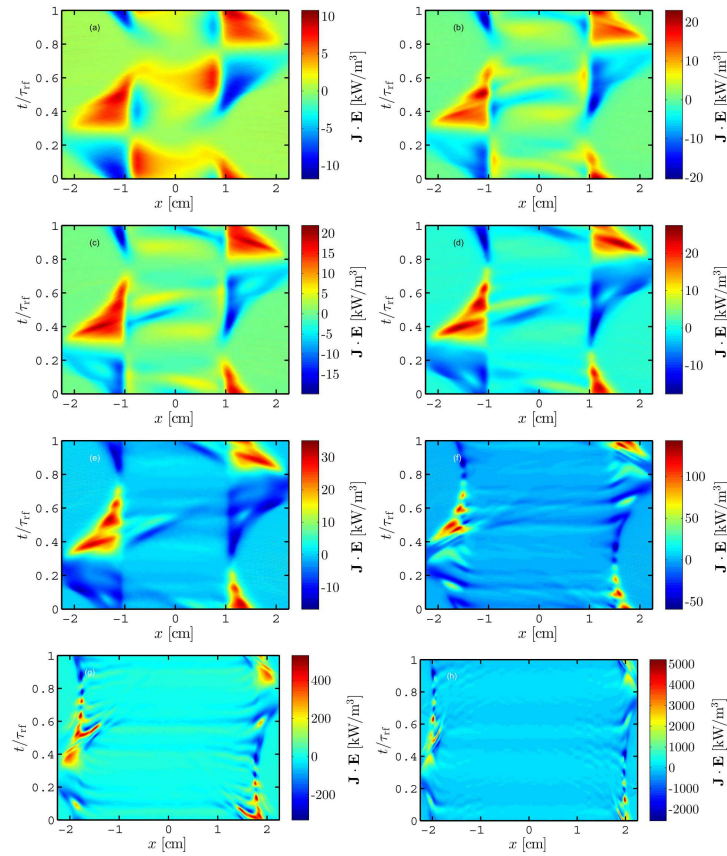


Figure 2. The spatio-temporal behavior of the electron power absorption for driving frequency (a) 12 MHz, (b) 18 MHz, (c) 19 MHz, (d) 19.5 MHz, (e) 20 MHz, (f) 27.12 MHz, (g) 50 MHz, and (h) 100 MHz, for a parallel plate capacitively coupled oxygen discharge at 10 mTorr with a gap separation of 4.5 cm driven by a 222 V voltage source.

Frá Gudmundsson et al. (2018)

Heimildir

Hér er tilvitnun í bók (Batchelor, 2000), doktorsritgerð (Monahan, 2007), og greinar (Sigurjonsson and Gudmundsson, 2008), og (Gudmundsson and Hecimovic, 2017), og ráðstefnugrein (Gudmundsson and Thorsteinsson, 2007).

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